Notice of Allowability	Application No.	Applicant(s)	
	10/080,539	KAGOSHIMA ET AL.	
	Examiner	Art Unit	
	Karla Moore	1763	
The MAILING DATE of this communication appeal claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIOF the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this applied or other appropriate communication IGHTS. This application is subject to	olication. If not included will be mailed in due course. The	HIS itiative
1. X This communication is responsive to RCE filed 3/30/04.			
2. 🔀 The allowed claim(s) is/are <u>1-25</u> .			
3. $igspace$ The drawings filed on <u>25 February 2002</u> are accepted by the	ne Examiner.		
<ul> <li>4.  Acknowledgment is made of a claim for foreign priority un</li> <li>a)  All b)  Some* c)  None of the:</li> <li>1.  Certified copies of the priority documents have</li> </ul>	been received.		
<ul><li>2.  Certified copies of the priority documents have</li><li>3.  Copies of the certified copies of the priority doc</li></ul>	· · · · · · · · · · · · · · · · · · ·		
International Bureau (PCT Rule 17.2(a)).	cuments have been received in this i	national stage application from t	ne
* Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DATE" on noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.  5. A SUBSTITUTE OATH OR DECLARATION must be submitined in INFORMAL PATENT APPLICATION (PTO-152) which give in CORRECTED DRAWINGS (as "replacement sheets") must (a) including changes required by the Notice of Draftspers 1) hereto or 2) to Paper No./Mail Date  (b) including changes required by the attached Examiner's Paper No./Mail Date  Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in the state of the such sheet.	ENT of this application.  itted. Note the attached EXAMINER's reason(s) why the oath or declarate the submitted.  on's Patent Drawing Review (PTO-standard PTO-standard PTO-st	S AMENDMENT or NOTICE OF tion is deficient.  948) attached  ffice action of the back) of d).	
<ol> <li>DEPOSIT OF and/or INFORMATION about the depose attached Examiner's comment regarding REQUIREMENT I</li> </ol>	sit of BIOLOGICAL MATERIAL n FOR THE DEPOSIT OF BIOLOGICA	nust be submitted. Note the AL MATERIAL.	
Attachment(s)  1. Notice of References Cited (PTO-892)  2. Notice of Draftperson's Patent Drawing Review (PTO-948)  3. Information Disclosure Statements (PTO-1449 or PTO/SB/0-Paper No./Mail Date  4. Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. ☐ Interview Summary Paper No./Mail Dat 8), 7. ☐ Examiner's Amendm	ė ´	

## **DETAILED ACTION**

## Allowable Subject Matter

- Claims 1-20 are allowed.
- The following is an examiner's statement of reasons for allowance.
- The prior art of record fails to fairly teach or suggest: A semiconductor manufacturing apparatus 3. comprising: an integrated measuring instrument for measuring the form or size of the element to be formed on a wafer; etching means for etching the wafer by using plasma generated under reduced pressure; ashing means for ashing the etched wafer; wetting means for wetting the etched wafer; drying means for drying the wafer which has gone through a wetting treatment; transport means for transporting wafers contained in a wafer cassette one by one successively along a depressurizable transport passage to the integrated measuring instrument and each working unit, including the etching means, the ashing means, the wetting means and the drying means, for treatment; and control means for controlling an order of treatment of each working unit, including the etching means, the ashing means and the drying means for transportation, using said transport means, along a depressurizable transport passage; wherein, depending upon an order of treatment designated by said control means, the etched wafer is ashed and then subjected to the wetting treatment, or the etched wafer is wetted and then subjected to an ashing treatment, and afterwards, the etched wafer is again measured by the integrated measuring means. Further, no other properly combinable piece of art was located to provide the proper motivation for adding the feature(s).

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Application/Control Number: 10/080,539

Art Unit: 1763

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should

be directed to Karla Moore whose telephone number is 571.272.1440. The examiner can normally be

reached on Monday-Friday, 8:30am-5:30pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor,

Gregory Mills can be reached on 571.272.1439. The fax phone number for the organization where this

application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application

Information Retrieval (PAIR) system. Status information for published applications may be obtained from

either Private PAIR or Public PAIR. Status information for unpublished applications is available through

Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should

you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC)

at 866-217-9197 (toll-free).

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10 June 2004

Parviz Hassanzadeh Primary Examiner Page 3

Art Unit 1763